

# CHEMIXX 30pm

## SEMI-AUTOMATIC WET PROCESSING SYSTEM

### BENEFITS

- ÷ Wafer up to 300mm
  - ÷ Square substrates up to 9x9 inch
  - ÷ Integrated media supply system
  - ÷ Up to two electric media arms
  - ÷ Wide range of nozzles available
  - ÷ BSR nozzle for DI-Water
  - ÷ Standard or customized chucks
  - ÷ Manually operated & safety interlocked process chamber door
  - ÷ Controller unit via 10inch touch screen
  - ÷ Small footprint
  - ÷ Designed for Institutes and R&D
- OPTIONAL: (DI) Chamber rinse



*CHEMIXX 30pm  
semi-automated  
wet processing system*

## FOR AQUEOUS BASED CHEMICALS

WAFERS UP TO 300MM



## PROPERTIES

- ÷ Round wafers up to  $\varnothing$  300mm
- ÷ Square substrates up to 9x9 inch
- ÷ Up to two electric media arms with z-axis movement for max. 6 lines each
- ÷ Heated media lines up to 60°C
- ÷ BSR (Back Side Rinse) nozzle for DI-Water
- ÷ Three integrated media supply systems for three different chemicals.
- ÷ Manual DI-water gun outside of the process chamber.
- ÷ Manually operated & safety interlocked process chamber door.
- ÷ Process chamber cover with flow holes.

**OPTIONAL:** with Chamber rinse (DI-water)

- ÷ Emergency stop button at systems front.

Semi-automatic controller unit:

- ÷ 10" color touch screen as user terminal
- ÷ Recipe editor to write, manage and configure
- ÷ Library function for recipes, flows, log file (e.g. error tracking history).
- ÷ User management with password-protected service access.
- ÷ Update & backup function via USB or intranet connection.
- ÷ Uninterruptible power supply (UPS) support for all data storage on SD-Card.

**IDEAL FOR COST-EFFECTIVE PROCESS OPERATION**

## CHEMIXX 30PM

### SINGLE PROCESSING CLEANING SYSTEM

Is a cost-effective wet processing system for versatile application. Two system variations are available, with or without DI-water chamber rinse. It provide users in R&D and industry with an easy to use and reliable system.

The sytem has an easy to operate user interface with all needed functions like, recipe programming, service, maintenance and user administration.

## ELECTRIC MEDIA ARMS

- ÷ Up to two electric media arms
- ÷ Each media arm can be equipped up to max. 6 media lines.
- ÷ All axis motor driven and fully programmable.

## NOZZLES

Aqueous based chemicals;

Equipped for chemical processing:

- ÷ Via puddle or spray nozzle
- ÷ Via atomizer nozzle
- ÷ Back side rinse nozzle

Equipped for mechanical processing:

- ÷ Via brush system
- ÷ High pressure or/and megasonic nozzle

UP TO TWO MEDIA ARMS

THREE MEDIA TANKS INTEGRATED

PROGRAMMABLE PARAMETERS

## TECHNICAL DATA (CHEMIXX 30pm)

### GENERAL

Substrate Size:	up to $\varnothing$ 300mm ( $\varnothing$ 12 inch) or 230 x 230 mm (9 x 9 inch)
Motor speed:	up to 3.000 rpm, programmable in 1 rpm steps*
Step time:	1 up to 999.9 sec, programmable in 0.1 sec steps
System frame:	made of powder-coated stainless steel
System housing:	made of PP white (optional FM 4910) and 4 adjustable feets
Process bowl:	made of PP natural
Process chamber:	made of PP white (optional PVDF)

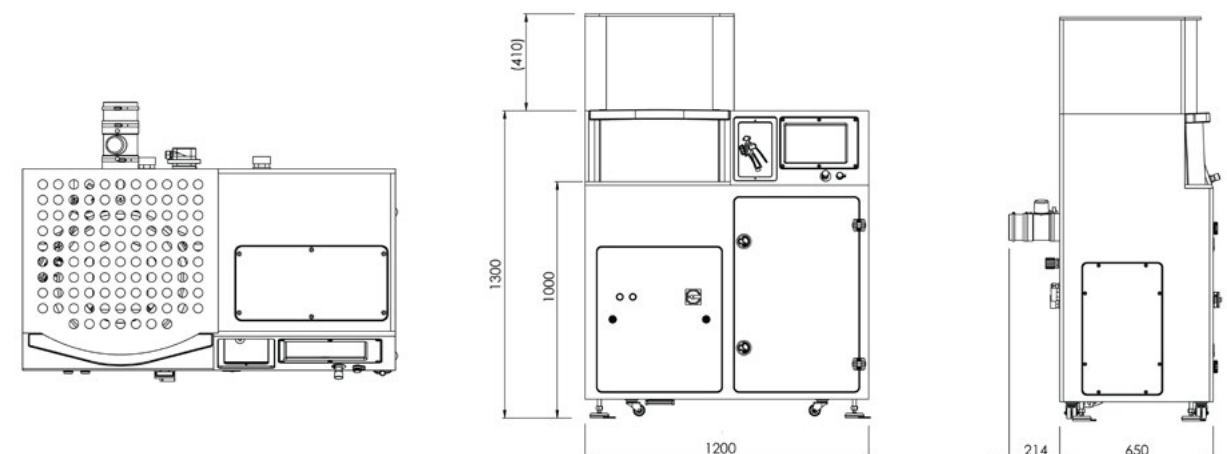
*\*depending on chuck design, substrate weight and load*

### REQUIREMENTS

Voltage:	400(208) VAC / 3 Phase / N / PE / 50(60) Hz
CDA:	8 bar, tube OD $\varnothing$ 10 mm
Vacuum:	-0.8 bar / -600 Torr, tube OD $\varnothing$ 10 mm
DI-Water:	4 bar, OD $\varnothing$ 16.7 mm (3/8")
Nitrogen (optional):	4 $\pm$ 2 bar, PFA tube OD $\varnothing$ 10 mm
Drain:	Gravity OD $\varnothing$ 38mm
Exhaust-process:	1x OD $\varnothing$ 110mm, 50-180 m <sup>3</sup> /h

**DIMENSIONS (WxDxH) approx.**

Housing: 1200 x 650/850 x 1300/1900 mm (47.2 x 25.6/33.5 x 51.2/74.8 inch)





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## OFFICE LOCATIONS

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*Data, design and specification of custom built machines depend on individual process conditions and can vary according to equipment configurations. Not all specifications may be valid simultaneously. Illustrations in this brochure are not legally binding. Osiris International GmbH reserves the right to change machine specifications without prior notice.*